## **ACKNOWLEDGEMENT RECEIPT**

## Electronic Version 1.1 Stylesheet Version v1.1.1

Title of Invention

## HIGH-PRESSURE PROCESSING CHAMBER FOR A SEMICONDUCTOR WAFER

Submision Type: Information Disclosure

Statement

Application Number:

10/680783

EFS ID: 81866

Server Response:

83

Confirmation Code

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First Named Applicant:

William Jones

Attorney Docket Number:

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From:

File Listing:

Doc. Name	File Name	Size (Bytes)	
			Produced
			(yyyymmdd)
us-ids	SSI_04001-usidst.xml	1541	2005-04-08
us-ids	us-ids.dtd	7763	2005-04-08
us <b>-id</b> s	us-ids.xsl	12026	2005-04-08
package-data	SSI_04001-pkda.xml	1707	2005-04-08
package-data	package-data.dtd	27025	2005-04-08
package-data	us-package-data.xsl	19263	2005-04-08
	69325		

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